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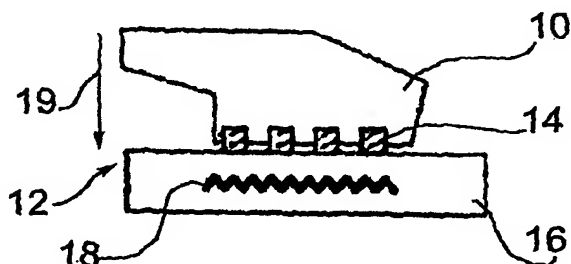
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(54) Title: A NANO IMPRESSION LITHOGRAPHIC PROCESS WHICH INVOLVES THE USE OF A DIE HAVING A REGION
ABLE TO GENERATE HEAT



(57) Abstract: A lithographic process for forming a pattern in
relief (20) on a mass (10) of polymeric material comprises the
steps of: preparing the mass (10) of polymeric material and a die
(12) having a surface region (14) facing towards the mass (10) of
polymeric material and which reproduces in negative the pattern
in relief (20); heating the die (12) and putting the mass (10) of
polymeric material into contact with the die (12) in any temporal
sequence, in such a way that the part of the mass (10) of poly-
meric material in contact with the surface zone (14) is subject to
softening; and separating the die (12) from the mass (10) of poly-
meric material on the surface of which the pattern in relief (20)
has been formed. The heating of at least one part of the die (12)
is obtained by generation of thermal energy upon dissipation of another form of energy in at least one region (16) of the die (12).